

AMENDMENTS TO THE CLAIMS

1-8 (Canceled)

9. (new) A coating method of forming a coating film on a surface of a substrate by making a coating liquid which is raised by capillary phenomenon in a nozzle into contact with the surface and make the coating liquid coated on the surface by the relative movement of the nozzle and the substrate,

comprising:

holding the substrate by a holding means so that the surface to be coated by the coating liquid faces downward;

bringing the holding means and a chucking means toward each other by moving at least one of the holding means and the chucking means, maintaining the surface to be coated facing downward;

chucking the substrate by the chucking means;

separating the holding means and a chucking means away from each other by moving at least one of the holding means and the chucking means; and

forming the coating film on the surface to be coated of the substrate by moving at least one of the nozzle and the chucking means in a horizontal direction.

10. (new) The coating method of claim 9 wherein, after said forming, the substrate is released from the chucking means in a state that a coated surface of the substrate faces downward.

11. (new) The coating method of Claim 9 wherein the chucking is carried out by vacuum means.

12. (new) The coating method of Claim 9 wherein during the forming of the coating film on the surface, controlling a distance between the nozzle and the surface so that the film thickness is uniform.

13. (new) The coating method of Claim 9 wherein before said forming, the nozzle is lifted so that the coating liquid is brought into contact with the surface, and the nozzle is descended an amount to determine a coating thickness.

14. (new) The coating method of Claim 9 wherein the holding means turns the substrate by a predetermined angle for attaching and detaching the substrate to and from the holding means.

15. (new) The coating method of claim 9, wherein the coating film comprises a photo-resist.

16. (new) The coating method of claim 9, wherein the substrate comprises a photo mask blank.

17. (new) A method of manufacturing a photo mask blank having a photo resist coating film on a surface, which film is formed, on a substrate, by making a coating liquid which is raised by capillary phenomenon in a nozzle into contact with the surface and making the coating liquid coated on the surface by the relative movement of the nozzle and the substrate,

the method comprising:

holding the substrate by a holding means so that the surface to be coated by the coating liquid faces downward;

bringing the holding means and a chucking means toward each other by moving at least one of the holding means and the chucking means, maintaining the surface to be coated facing downward;

chucking the substrate by the chucking means; and

separating the holding means and the chucking means away from each other by moving at least one of the holding means and the chucking means; and

forming the coating film on the surface to be coated of the substrate by moving at least one of the nozzle and the chucking means in a horizontal direction.